

## Description

The equipment is used for an automatic process of etching and cleaning small Si-wafers for research tasks in various process chemicals. The operator will prepare loads of etching baths and will place the baskets with silicon substrates sized 2" in positions for collection.

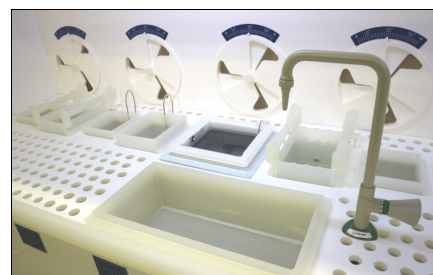
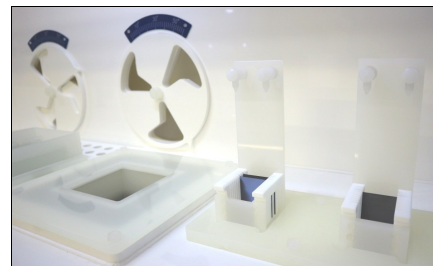
Having the automatic process been triggered, the wafers are gradually dipped in etching baths and in rinse baths and they can be dried in a hot-air circulation dryer at the end of the technological process.

Handling in the working area of the line is ensured by a built-in portal manipulator. The course of the process is managed by an industrial PLC which is controlled via a touch screen.

The system enables a simple creation of formulas which comprises the use of individual process baths and rinse baths, the drier and adjustment of process temperatures and times.

## Facts and interesting things:

- A skeleton of the cabinet is made from chemically resistant polypropylene.
- Individual process baths are in various versions according to the chemicals used for etching. Some of them are fitted with an built-in electric heater with temperature regulation.
- baths for etching with hydrofluoric acid have a separate collecting system and a collection canister for wastes.
- Two rinse baths are connected to the DEMI water distribution network and they have bottom filling. They are fitted with a pair of adjustable lateral-jet showers and with conductivity measurement of waste water in order to check the technical efficiency of the rinse.
- The hot rinse tub is connected to the supply of ozonized water and is heated to 80°C.
- The last pair of the rinse baths is a gravity cascade version.
- The air circulation in the dryer is ensured by a radial blower which forces the air to go through a built-in HEPA filter. There is a space to drain the condensate, on the bottom of the cabinet.
- An electric switchboard, a pneumatic terminal are built-in from the rear side of the line in a separate manner and the waste system of chemicals in the bottom part.



## Basic technical data

Length:	4000	mm
Width:	1220	mm
Height:	2660	mm
Weight:	860	kg
Power supply:	3 NPE 400/230V AC 50Hz TN-S	